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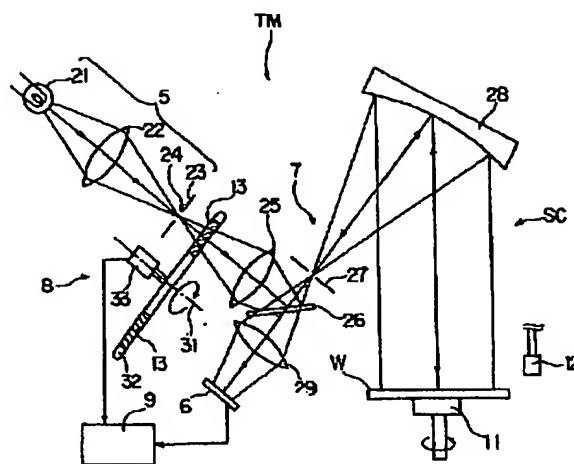
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TITLE : SUBSTRATE PROCESSING DEVICE



ABSTRACT : **PROBLEM TO BE SOLVED:** To provide a substrate processing device wherein, even if kind of chemical which is supplied to a substrate is changed, rotational speed of a substrate which is suitable to the chemical is easily decided for forming an even chemical thin film on the surface of substrate.

SOLUTION: A spin coater SC comprising a spin chuck 11 which rotates while chucking holding the backside of a substrate W and a resist supply nozzle 12 for supplying resist to the surface of substrate W held by the spin chuck 11, a light source part 5, a CCD camera 6, an optical system 7, a filter switching means 8, and a processing part 9 are provided, while a film thickness measuring unit TM for collectively measuring thickness of the thin film of resist formed on the surface of substrate W at the spin coater SC in a predetermined area on the surface of substrate W is provided.

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